

氮化鎳快速熱退火處理設備

Instrument introduction



- ✧ Wafer Size : Small ~ 8 inch
- ✧ Wafer loading : Manually
- ✧ Type : Desktop , Atmospheric Rapid Thermal Processing System
- ✧ Temperature : 100 ~ 800 °C or 450 ~1000 °C
- ✧ Gas Lines : N2 and O2 and H2 5% in N2 MFC